

Fig. 1 (Prior Art)

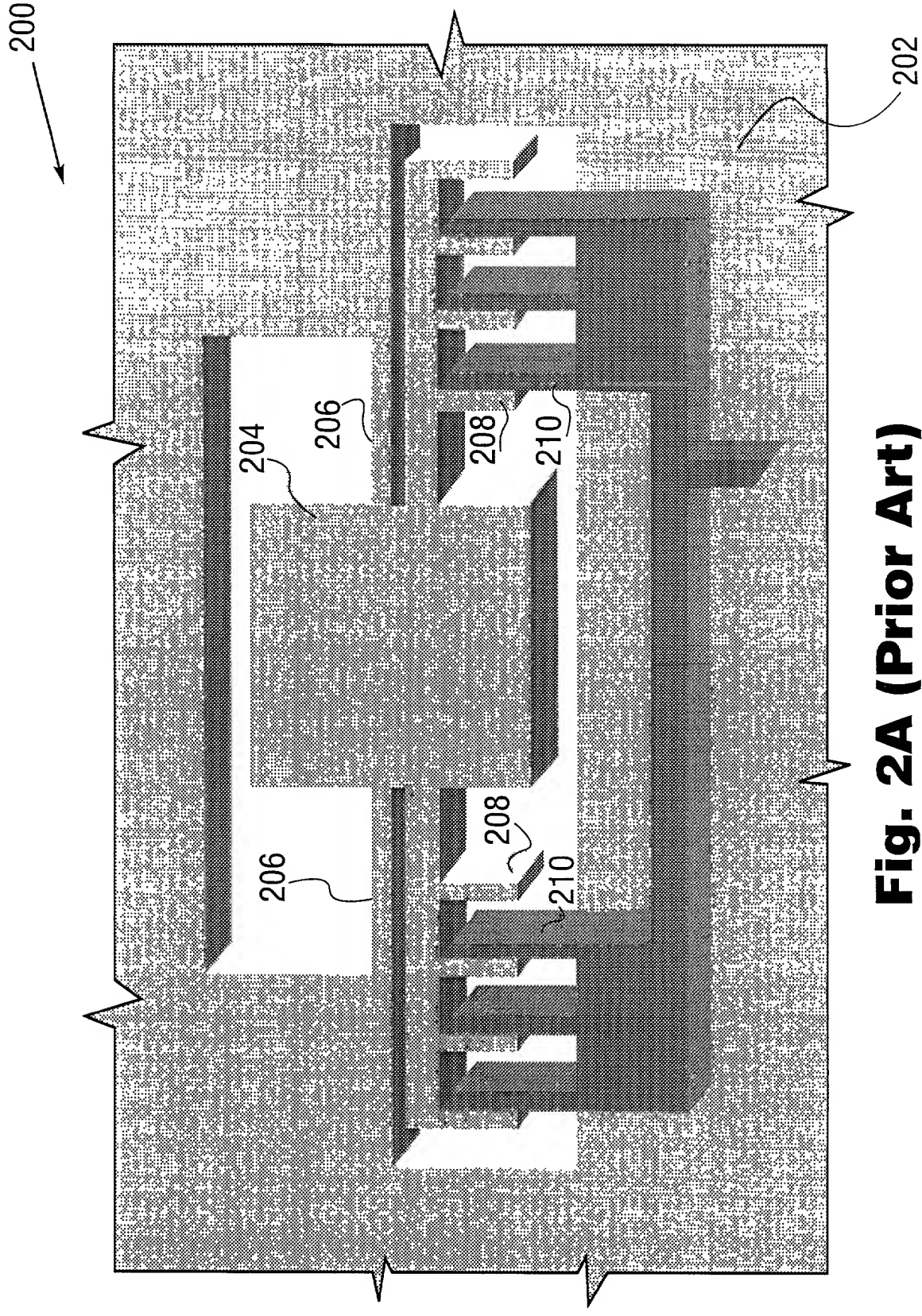


Fig. 2A (Prior Art)

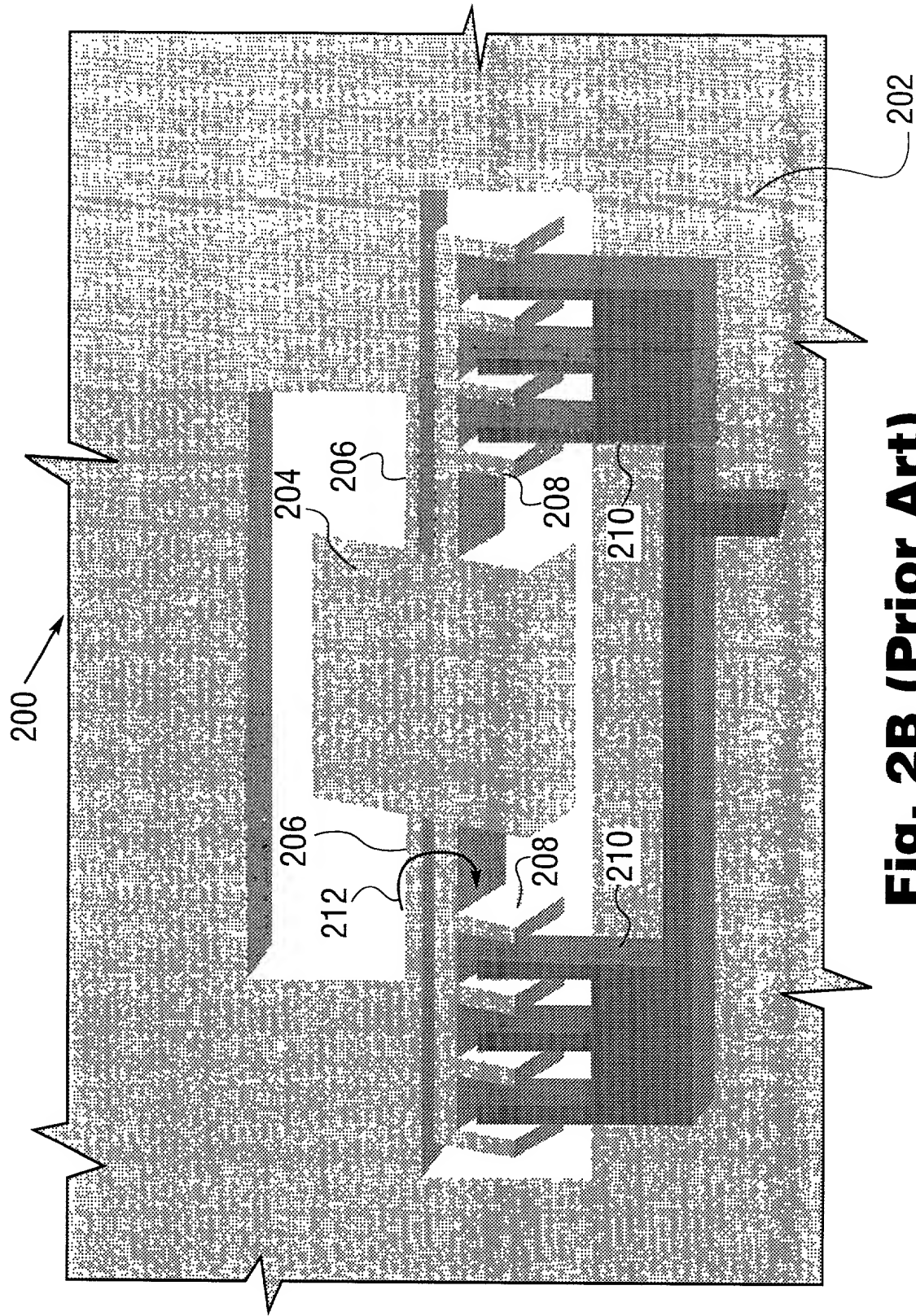


Fig. 2B (Prior Art)

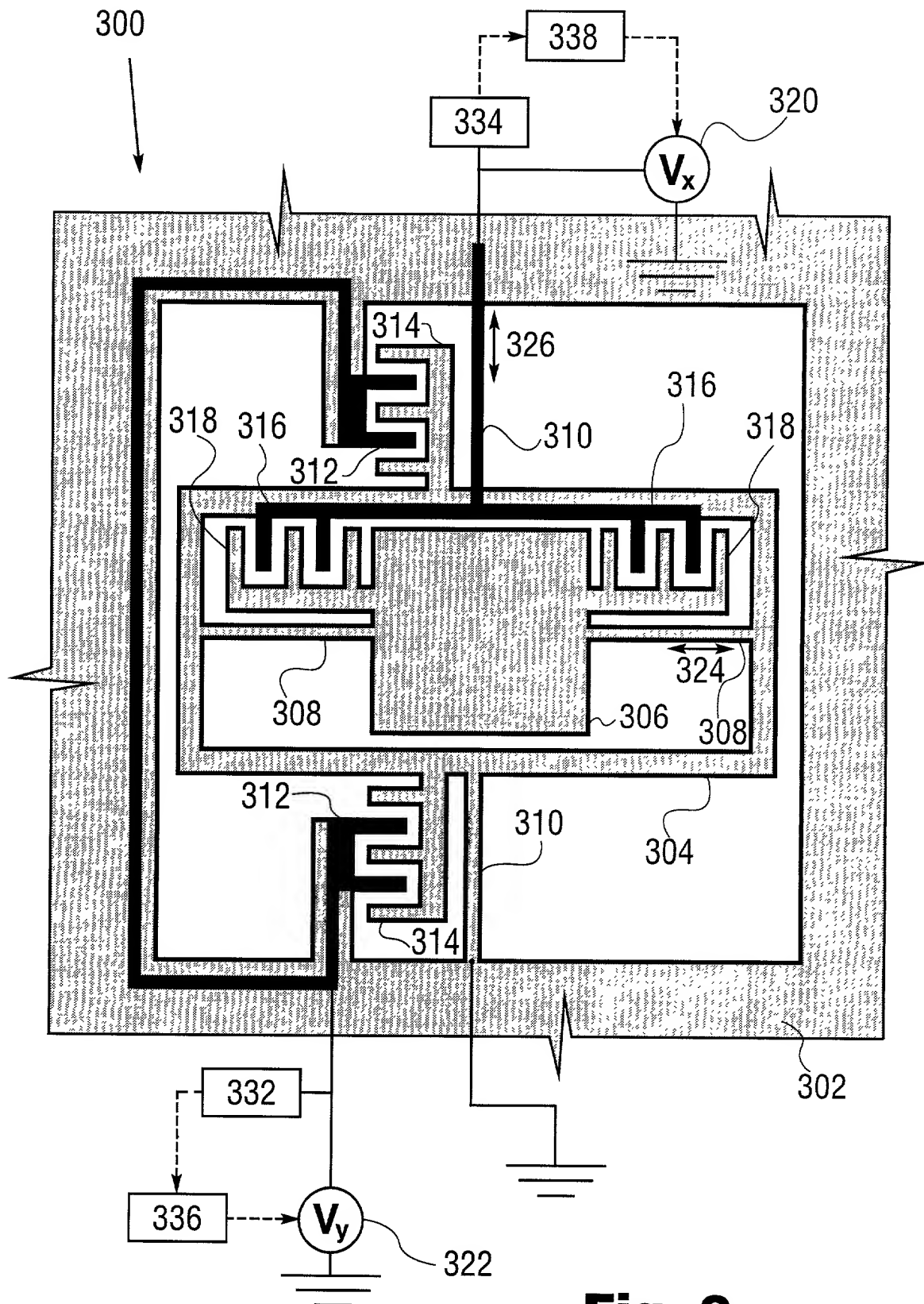


Fig. 3

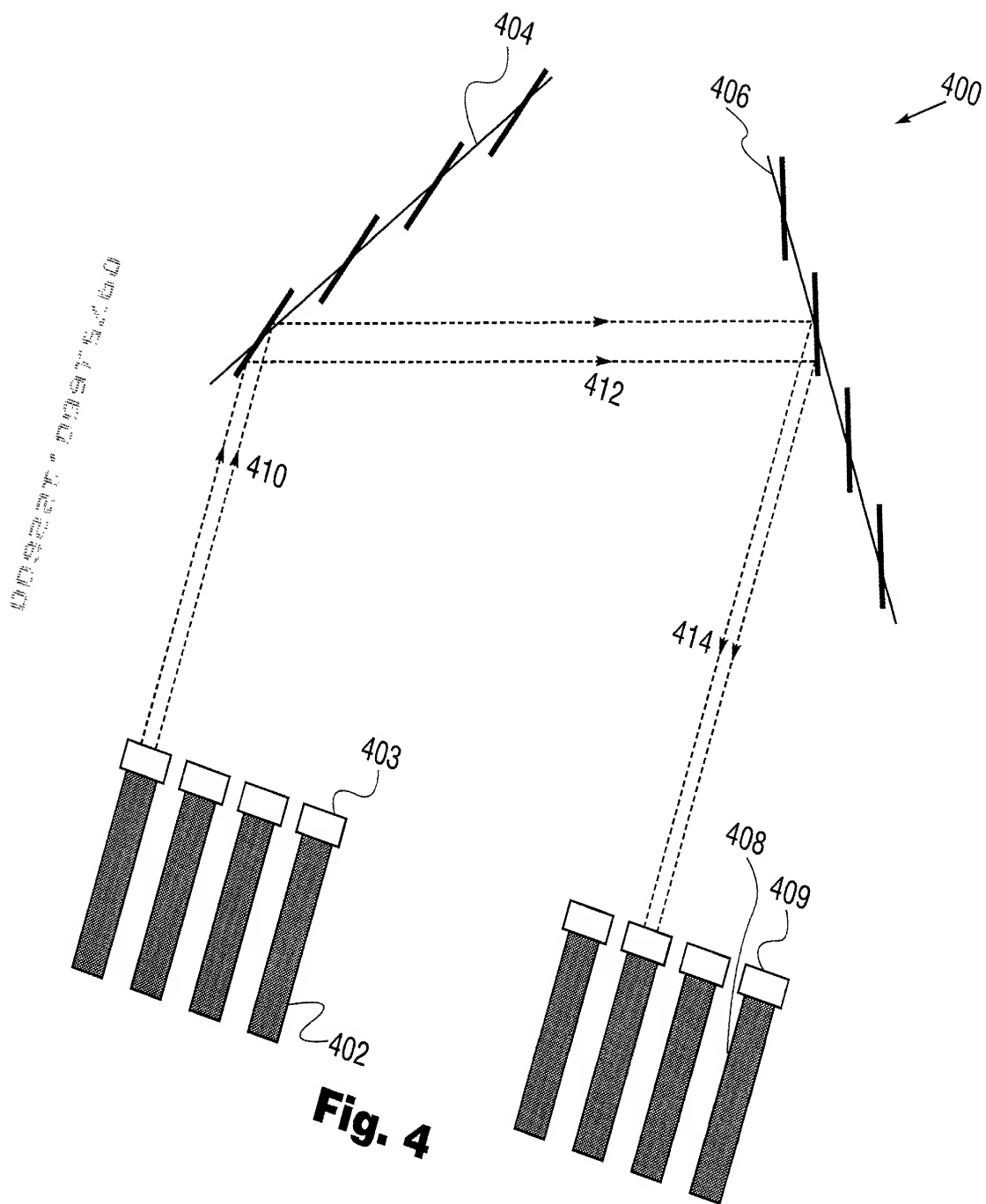


Fig. 4

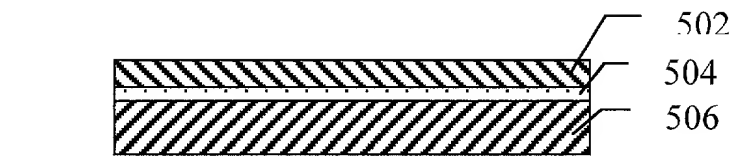


Fig. 5A

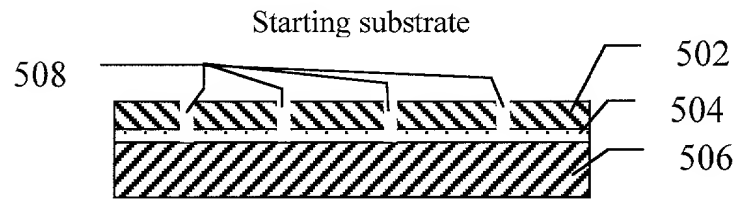


Fig. 5B

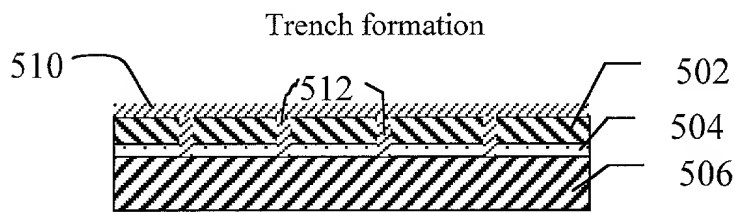


Fig. 5C

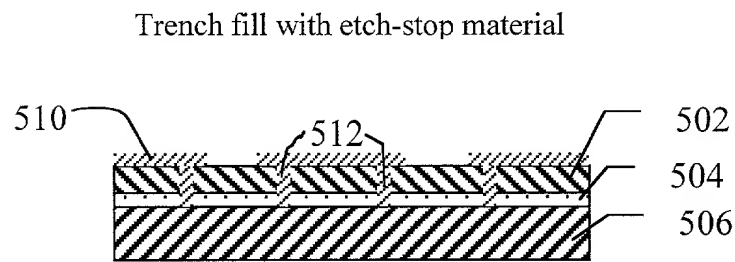


Fig. 5D

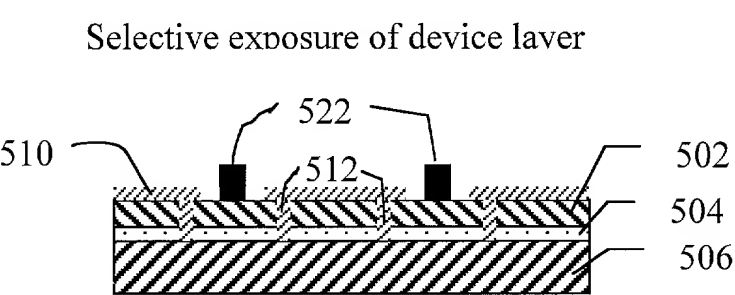


Fig. 5E

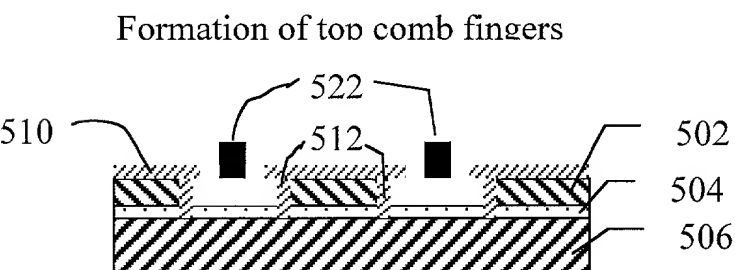


Fig. 5F

Starting substrate

Trench formation

Trench fill with etch-stop material

Selective exposure of device layer

Formation of top comb fingers

Isotropic release etch

